

REPORT DOCUMENTATION PAGE

Form Approved
OMB No. 0704-0188

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1. REPORT DATE (DD-MM-YYYY)

2. REPORT TYPE

Technical Paper

3. DATES COVERED (From - To)

4. TITLE AND SUBTITLE

5a. CONTRACT NUMBER

5b. GRANT NUMBER

5c. PROGRAM ELEMENT NUMBER

6. AUTHOR(S)

5d. PROJECT NUMBER

2303

5e. TASK NUMBER

M1A3

5f. WORK UNIT NUMBER

346127

7. PERFORMING ORGANIZATION NAME(S) AND ADDRESS(ES)

8. PERFORMING ORGANIZATION
REPORT

9. SPONSORING / MONITORING AGENCY NAME(S) AND ADDRESS(ES)

Air Force Research Laboratory (AFMC)
AFRL/PRS
5 Pollux Drive
Edwards AFB CA 93524-7048

10. SPONSOR/MONITOR'S
ACRONYM(S)

11. SPONSOR/MONITOR'S
NUMBER(S)

12. DISTRIBUTION / AVAILABILITY STATEMENT

Approved for public release; distribution unlimited.

13. SUPPLEMENTARY NOTES

14. ABSTRACT

20030127 197

15. SUBJECT TERMS

16. SECURITY CLASSIFICATION OF:

17. LIMITATION
OF ABSTRACT

18. NUMBER
OF PAGES

19a. NAME OF RESPONSIBLE
PERSON

Leilani Richardson

a. REPORT

b. ABSTRACT

c. THIS PAGE

Unclassified

Unclassified

Unclassified

A

19b. TELEPHONE NUMBER

(include area code)

(661) 275-5015

Standard Form 298 (Rev. 8-98)

Prescribed by ANSI Std. Z39.18

2303M1A3

MEMORANDUM FOR PRS (In-House Contractor Publication)

FROM: PROI (STINFO)

08 May 2002

SUBJECT: Authorization for Release of Technical Information, Control Number: **AFRL-PR-ED-VG-2002-101**
Tim Haddad (ERC) and Brent Viers (PRSM), "Organic Polymers Modified with Inorganic Polyhedra"

Canadian Society for Chemistry
(2-5 June 2002, Vancouver, Canada) (Deadline: 31 May 2002)

(Statement A)

ORGANIC POLYMERS MODIFIED WITH INORGANIC POLYHEDRA.

Timothy S. Haddad and Brent D. Viers
ERC Inc., Air Force Research Lab,
10 E Saturn Boulevard
Edwards Air Force Base, CA 93524

Nanostructured composites of thermoplastics and inorganic clusters have been developed by incorporating polyhedral oligomeric silsesquioxane (POSS) macromers into organic polymers. These hybrid inorganic/organic thermoplastics based on styrenes, acrylics, imides, norbornenes or siloxanes, are reinforced by covalently linking monodisperse inorganic POSS clusters to the polymer backbone. A typical POSS-macromer, $R_7P(Si_8O_{12})$, is a well-defined octomeric polyhedron containing a single "P" functionality for polymerization and seven "R" groups to solubilize and compatibilize the inorganic filler with the organic matrix. A nanoreinforcement effect from the POSS groups is strongly influenced by the seven "R" groups (cyclopentyl, cyclohexyl, isobutyl or phenyl). Covalently attached POSS groups result in significant change to the observed characteristic relaxation time of the polymer; rheological measurements on molten polymer indicate that interactions between the POSS groups generate a reversible network material with rubbery properties. TEM images show that the inorganic POSS moieties associate to form a nanoscale network within the polymer matrix.

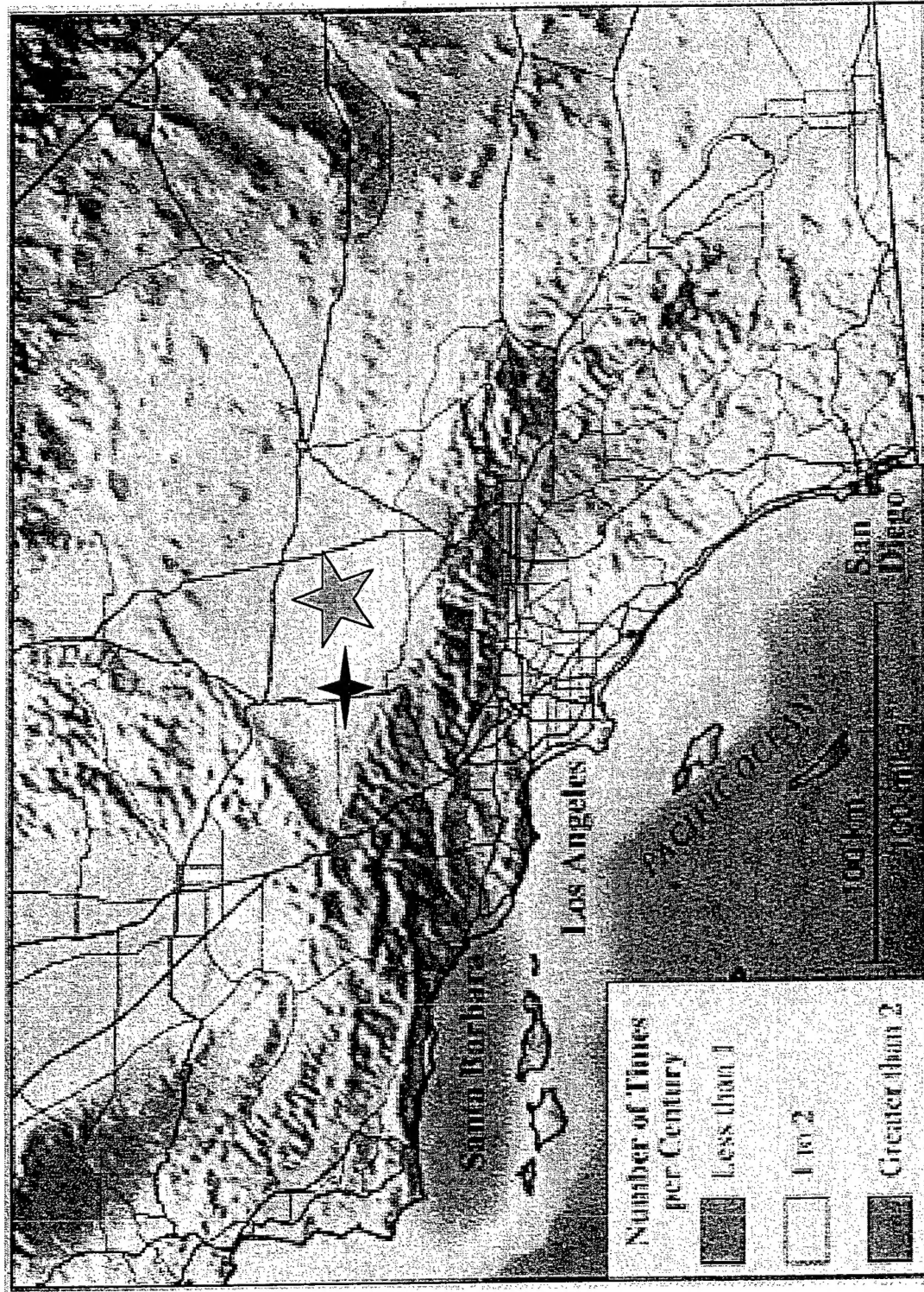
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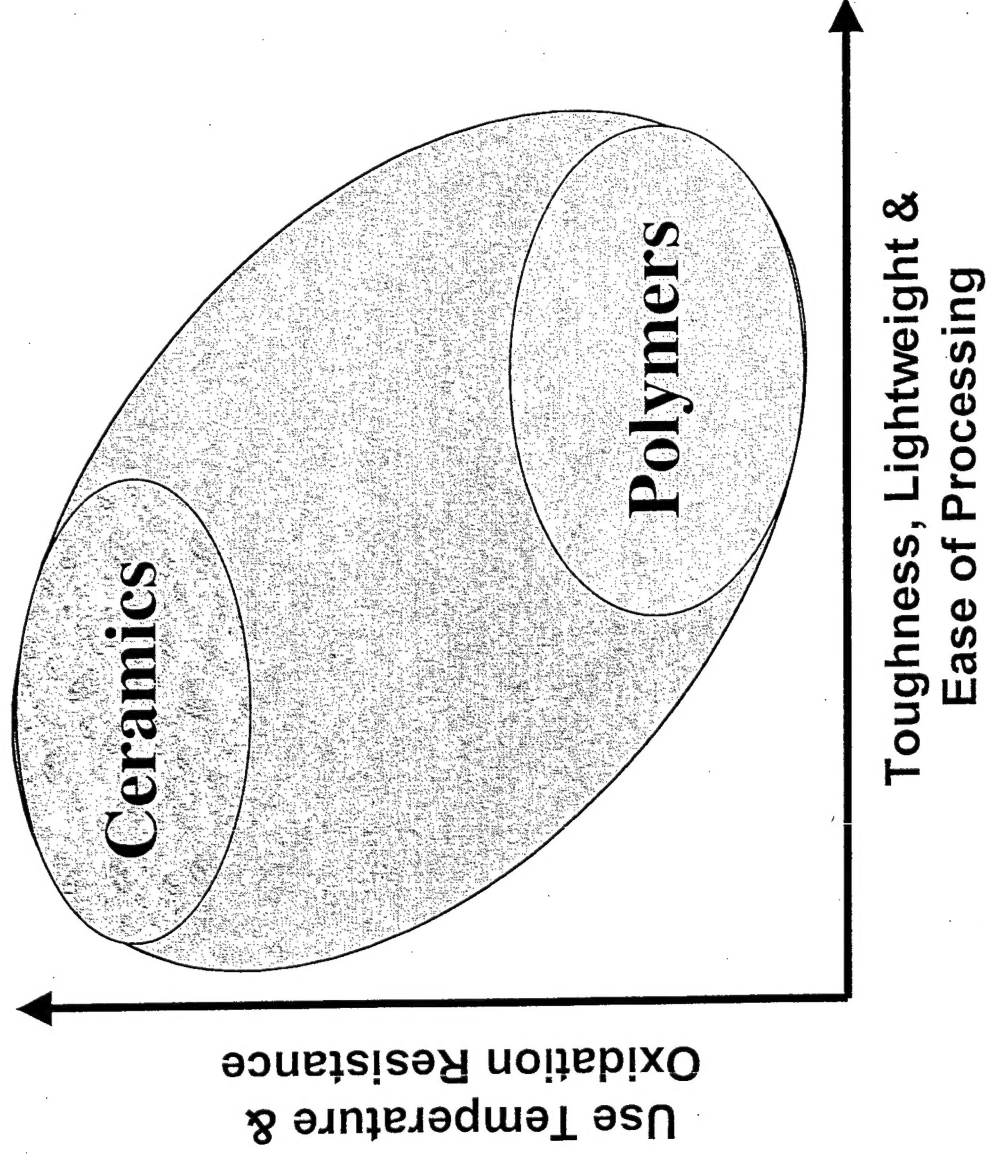
ORGANIC POLYMERS MODIFIED WITH INORGANIC POLYHEDRA

**Tim Haddad and Brent Viers
ERC Inc., Air Force Research Lab**

Edwards Air Force Base, CA



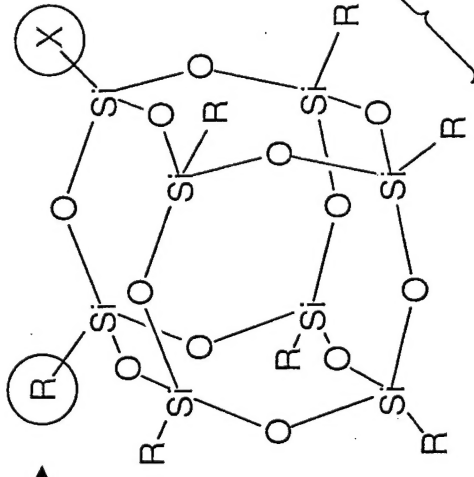
Hybrid Inorganic/Organic Polymers



Hybrid plastics can bridge the differences between ceramics and polymers

Anatomy of a POSS Macromer

Nonreactive organic (R) groups for solubilization and compatibilization.

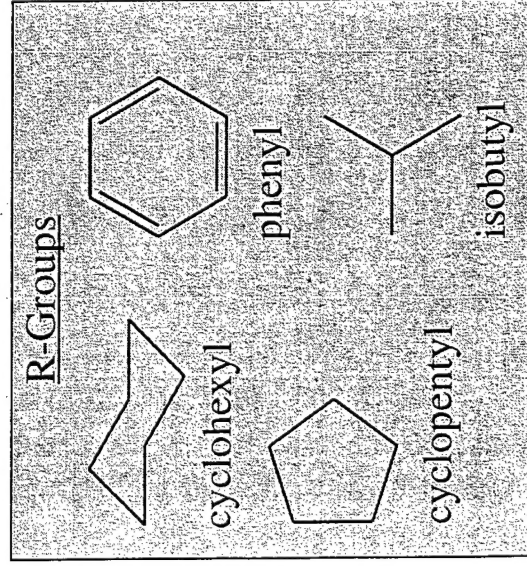


May possess one or more functional groups suitable for polymerization or grafting.



Nanosopic in size with an Si-Si distance of 0.5 nm and a R-R distance of 1.5 nm.

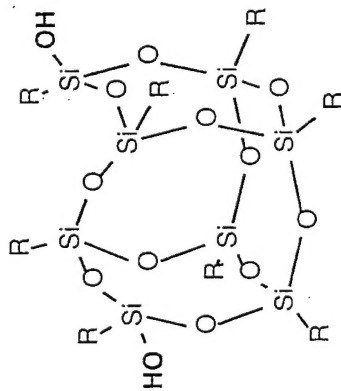
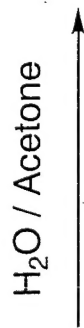
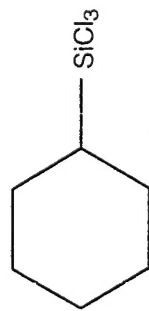
Thermally and chemically robust hybrid (organic-inorganic) framework.



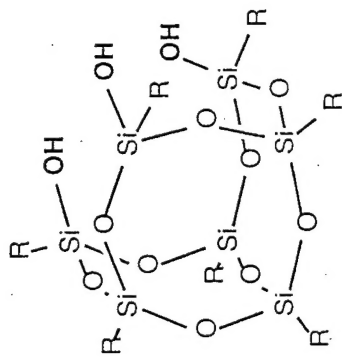
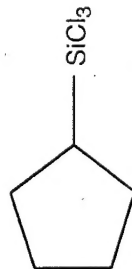
Precise three-dimensional structure for molecular level reinforcement of polymer segments and coils.



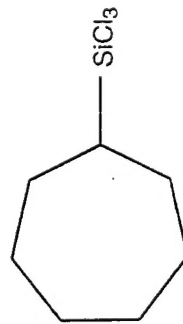
POSS Silanol Synthesis



R = Cyclohexyl

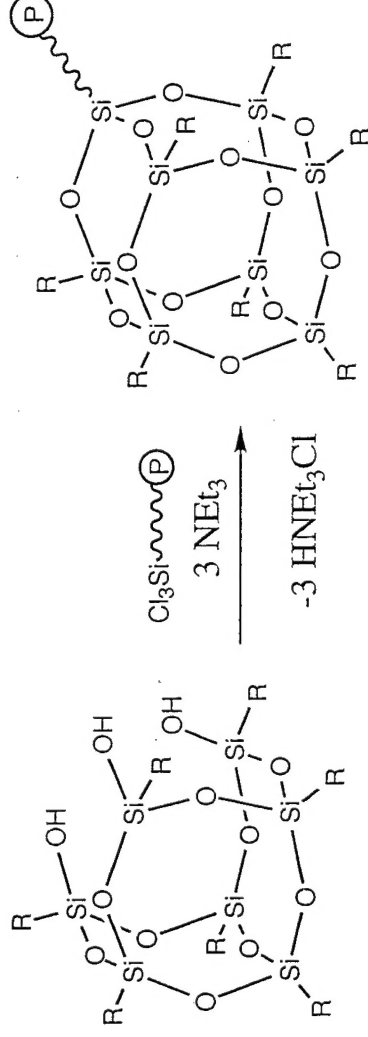
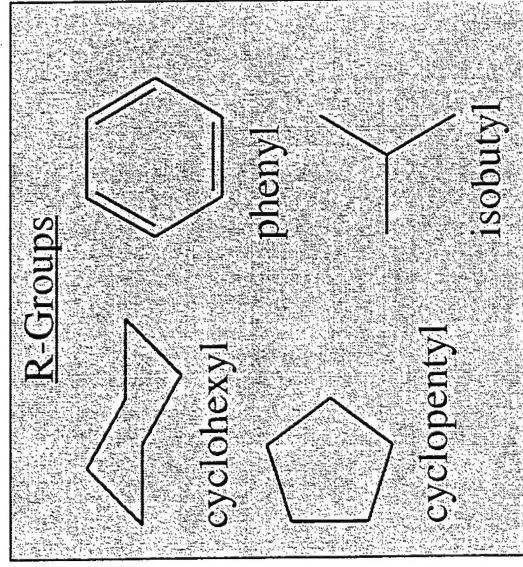


R = Cyclohexyl
Cyclopentyl
Cycloheptyl



Brown & Vogt: JACS, 1965, p. 4313
Fehér et al: JACS, 1989, p 1741;
Organometallics, 1991, p 2526

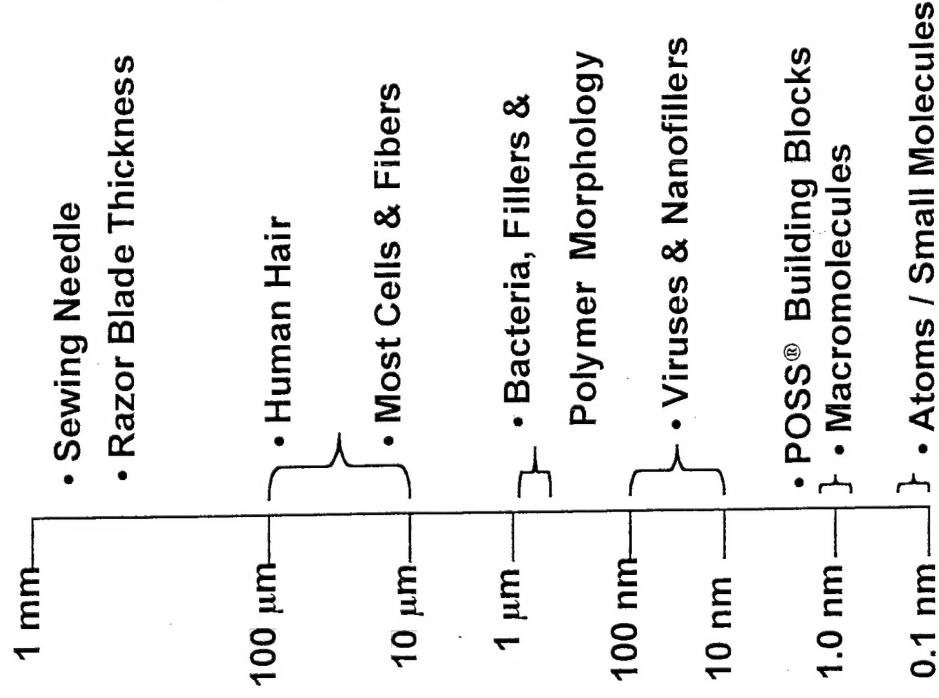
POSS Macromers For Nanocomposites



Halides	Nitriles	Silanes	Styryls
Alcohols	Amines	Silanol	α -olefins
Esters	Isocyanates	Silylchlorides	Acrylics
Bisphenols	Epoxides		Norbornenyls

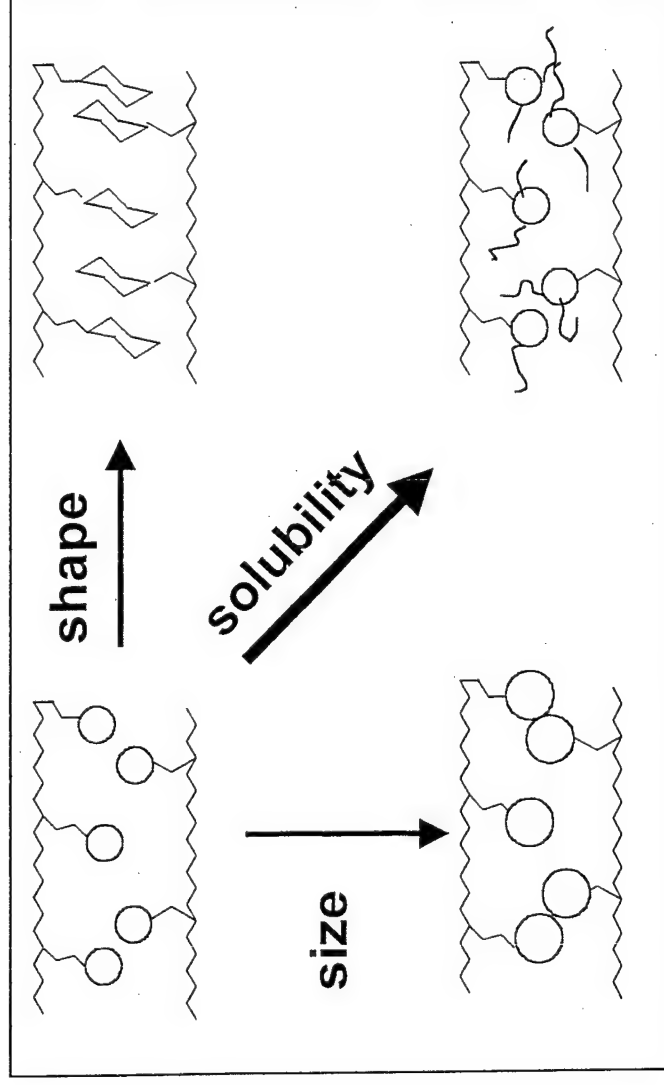
POSS-based macromers are now available through either **Geleste** or **Aldrich**
 POSS technology is commercialized by **Hybrid Plastics** in Fountain Valley CA

Why POSS and Why Nano?



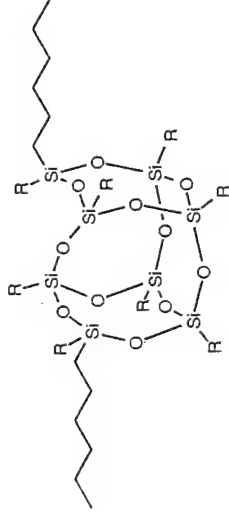
Field	Property	Critical Length
Electronics	Tunneling	1-100 nm
Optical	Quantum Well	1-100 nm
	Wave Decay	10-1000 nm
Polymers	Primary Structure	0.1-10 nm
	Secondary Structure	10-1000 nm
Mechanics	Dislocation Interaction	1-1000 nm
	Crack Tip Radius	1-100 nm
	Entanglement Rad.	10-50 nm
Therm-Mech.	Chain Motion	0.5-50 nm
Nucleation	Defect	0.1-10 nm
	Critical Nucleus Size	1-10 nm
	Surface Corrugation	1-10 nm
Catalysis	Surface Topology	1-10 nm
Biology	Cell Walls	1-100 nm
Membranes	Porosity Control	0.1-5 nm

Structure-Property Relationships

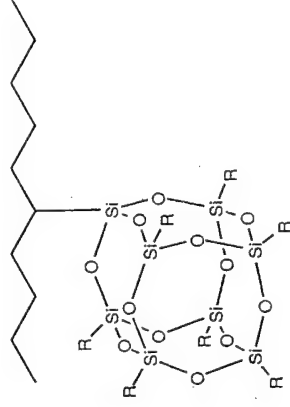


- Maximizing property enhancements through changes at the nano level
- Polymer miscibility vs. POSS/POSS interactions

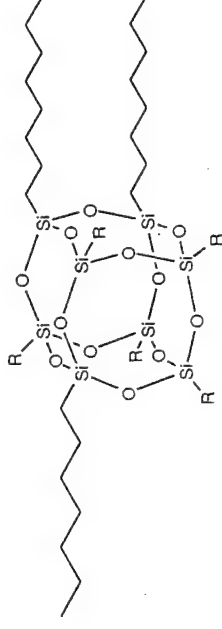
POSS Polymer Incorporation



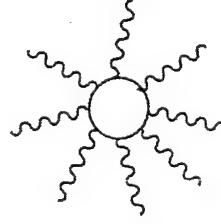
POSS Bead



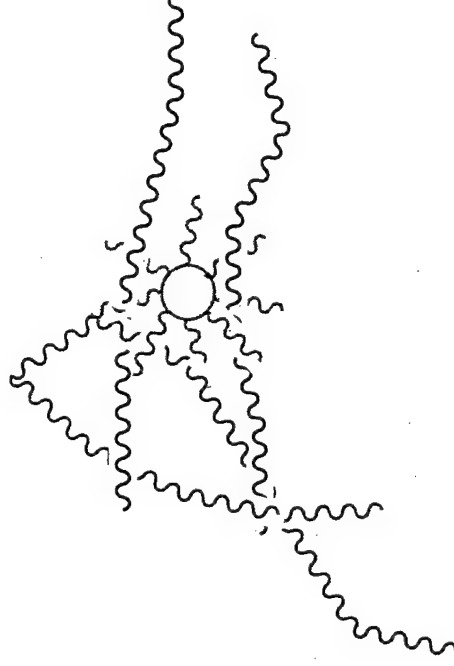
POSS Pendant



POSS Crosslinking

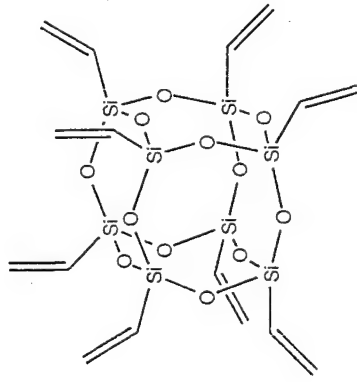


POSS Blending

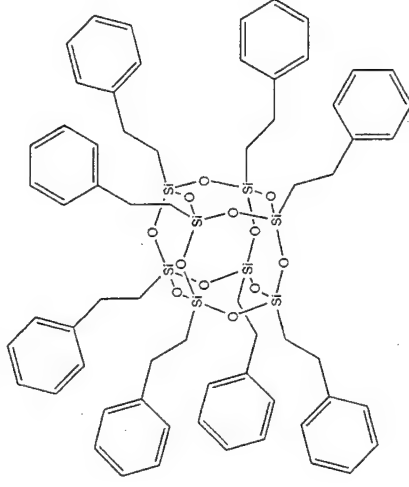


Size & Shape

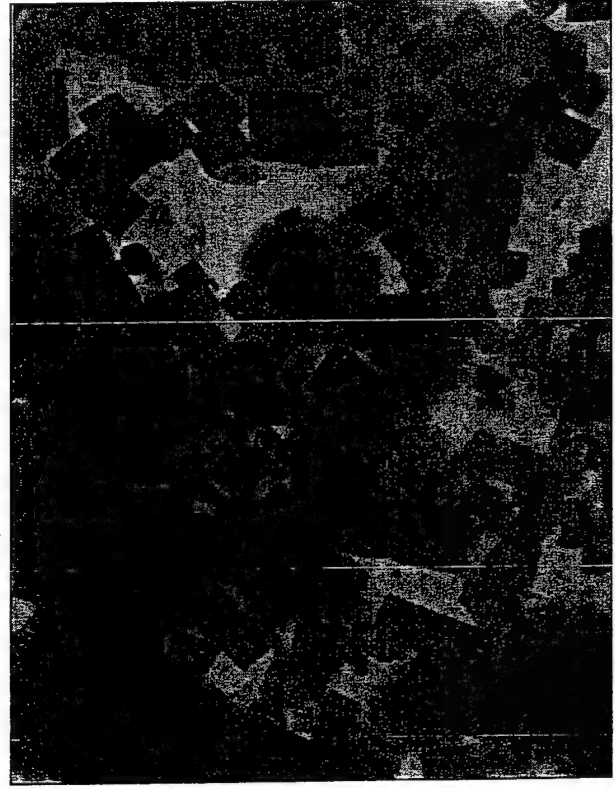
50 Wt % POSS Blends in 2 Million MW Polystyrene



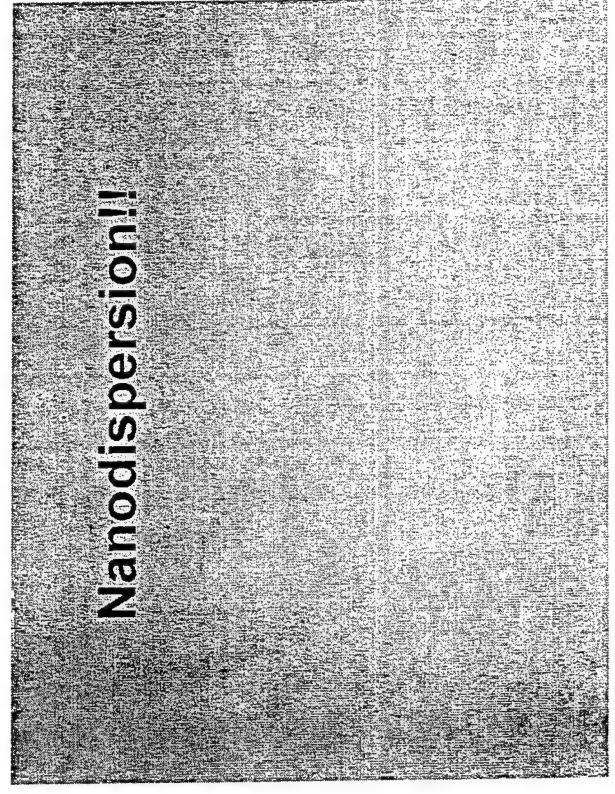
Vi₈T₈



Phenethyl₈T₈

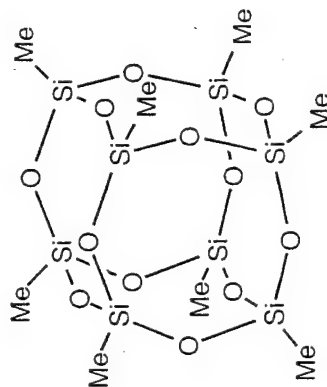
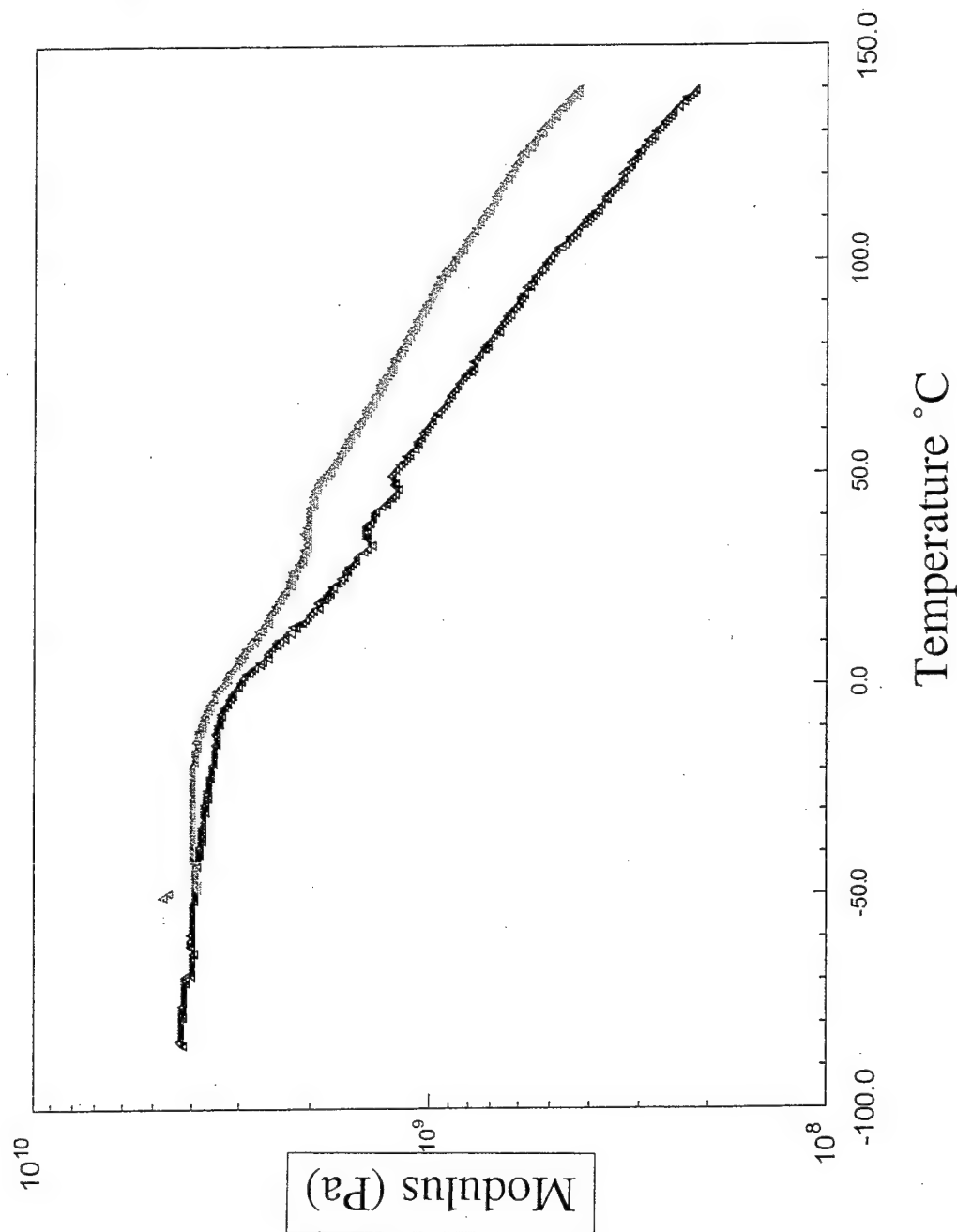


1 μm



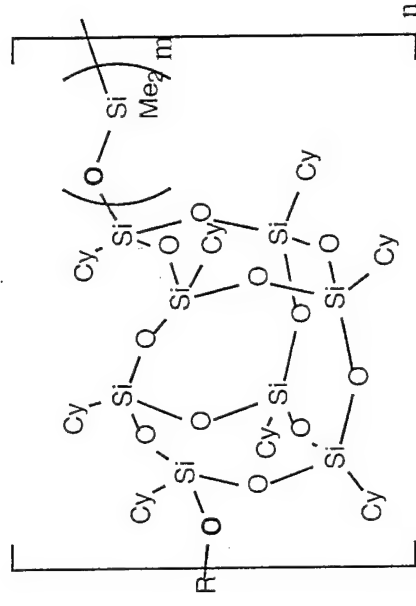
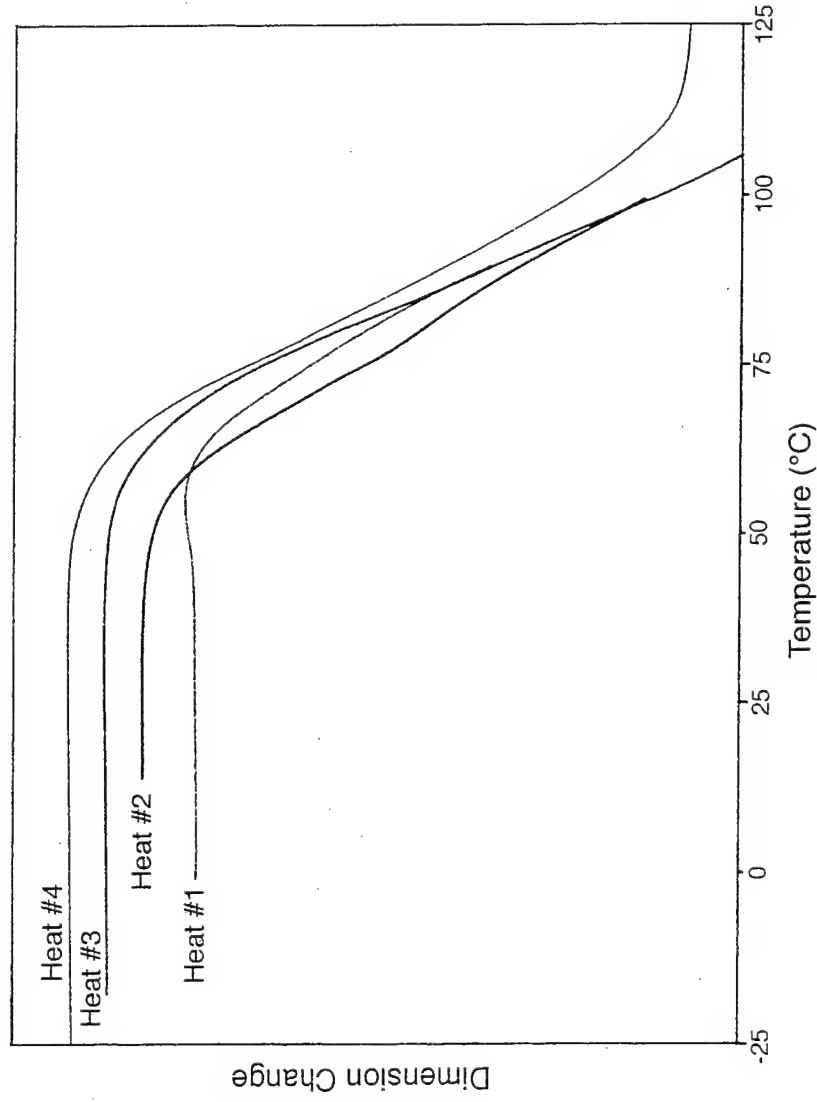
Nanodispersion!!

DMA of 10 Wt % POSS in isotactic Polypropylene

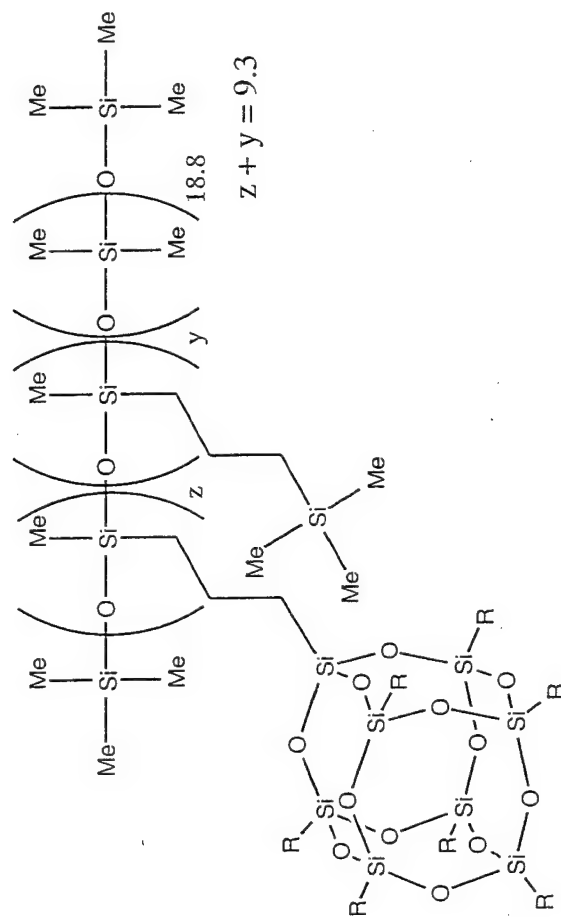
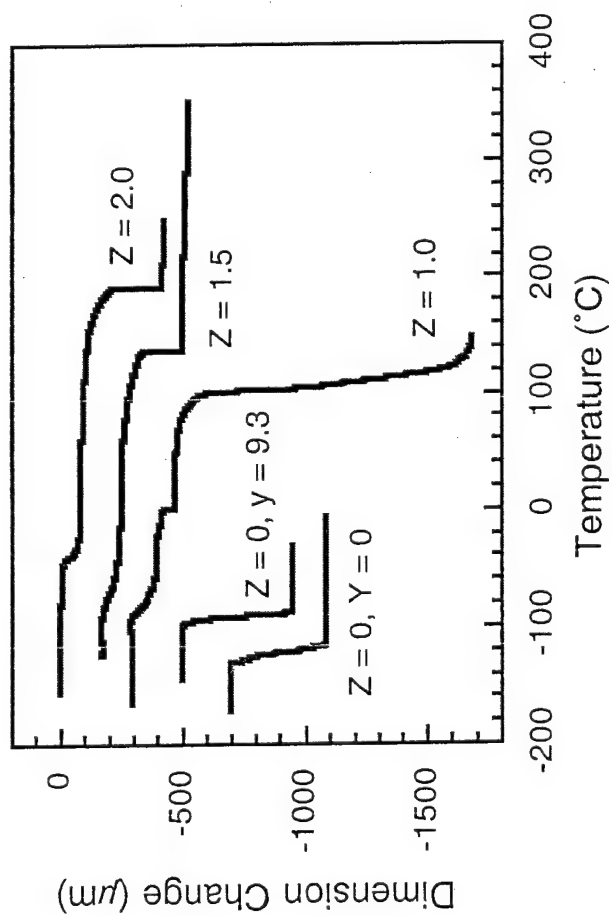


PDMS-POSS TMA Characterization

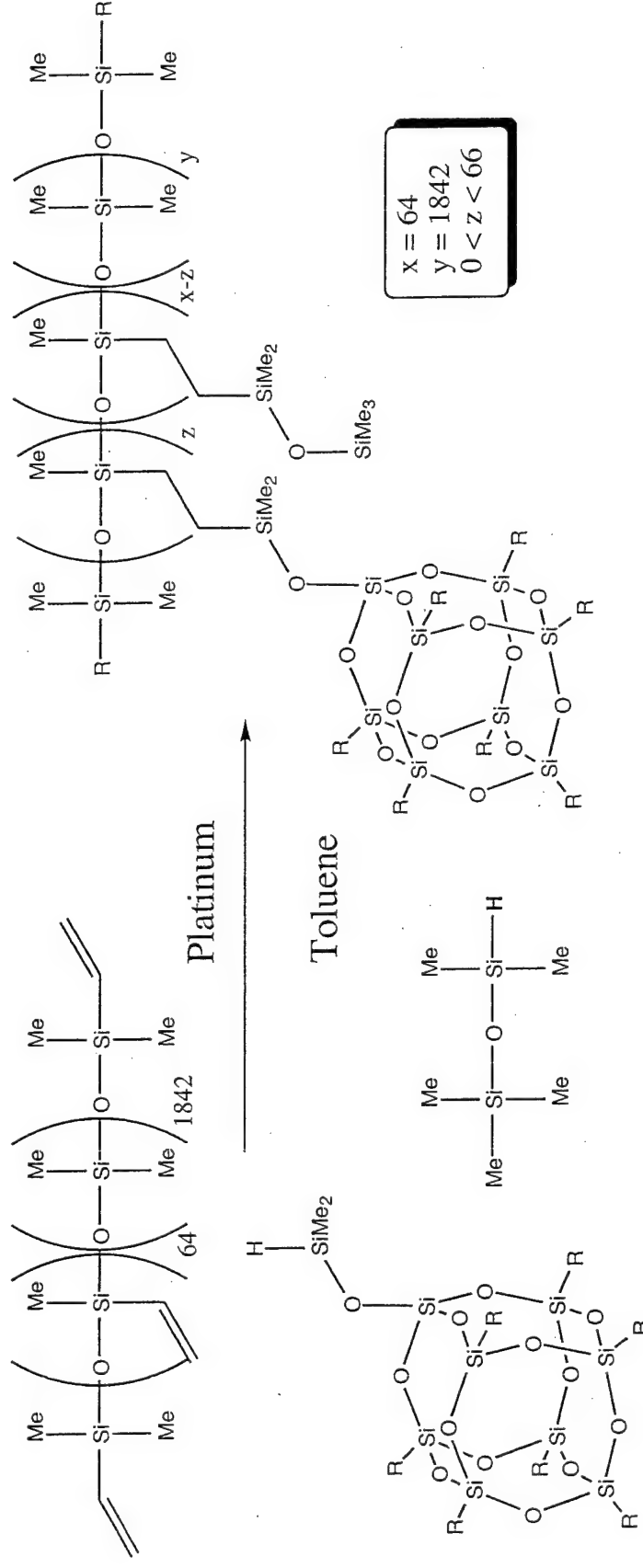
The POSS/Siloxane copolymers with four or more Si-O repeat units in the siloxane segment have softening temperatures well below the decomposition temperatures.



TMA of Pendent POSS-Siloxanes



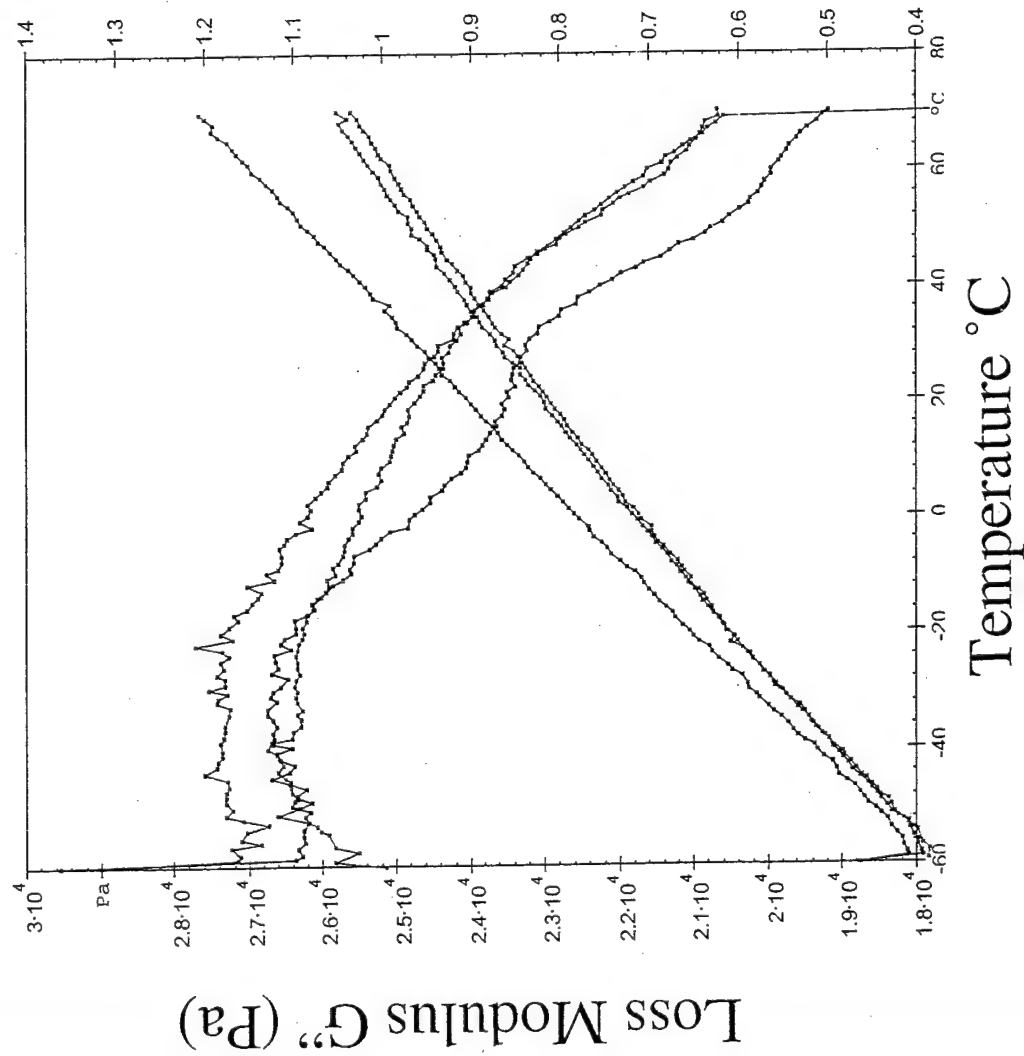
Hydrosilation to High MW PDMS



There are about 7 POSS-macromers per PDMS chain

Used 5 weight % POSS

Comparison of Three T8-POSS Macromers

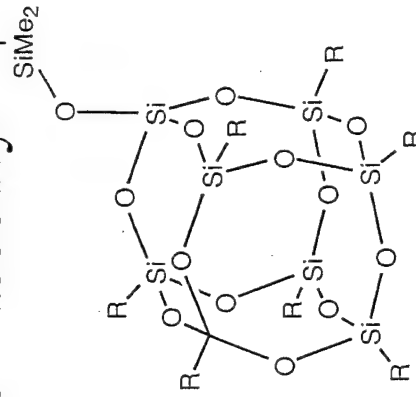


PDMS + 5 wt % POSS

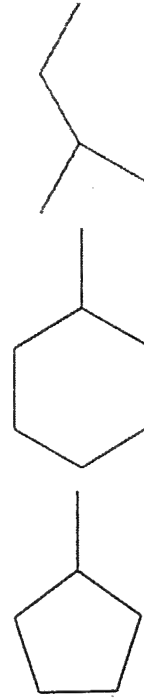
Blue = cyclopentyl

Red = cyclohexyl

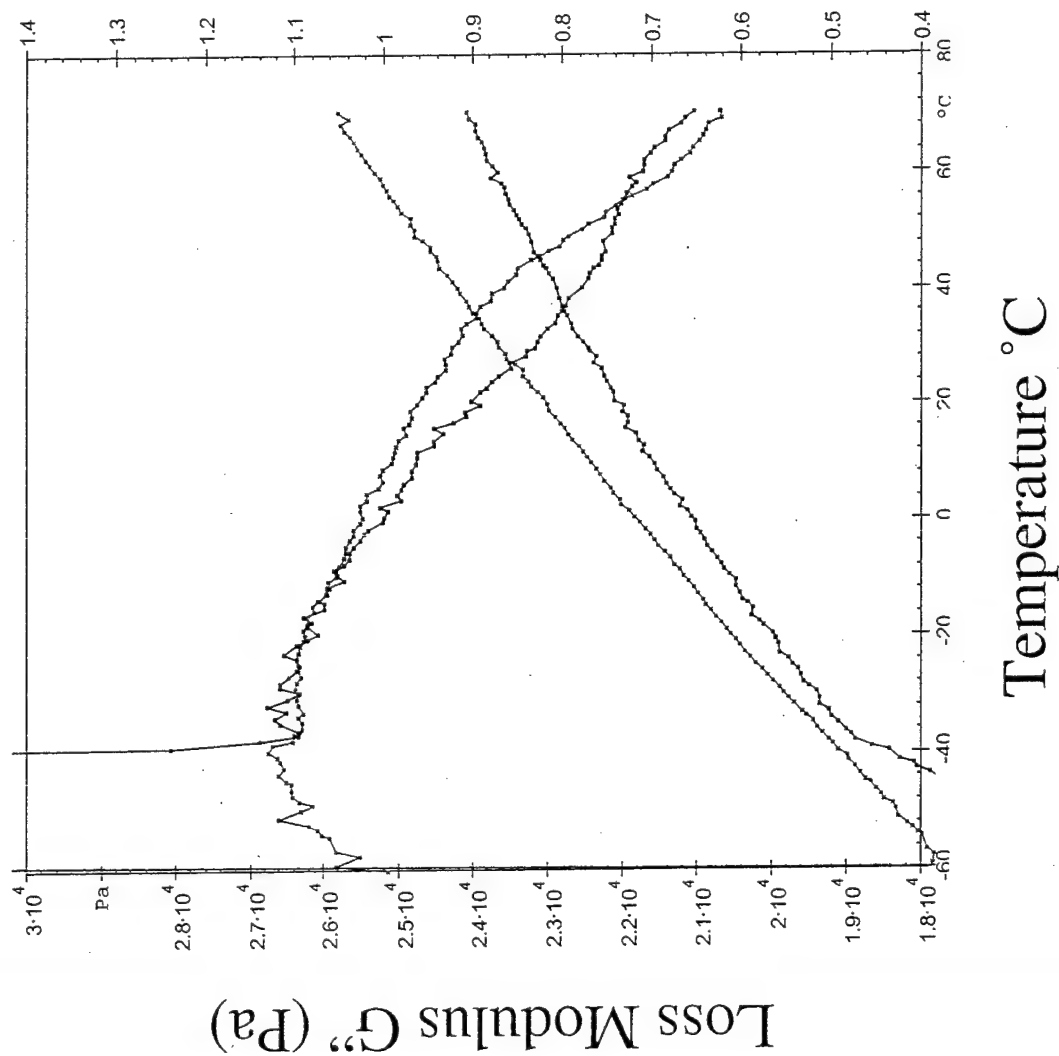
Purple = isobutyl



$\tan(\delta)$

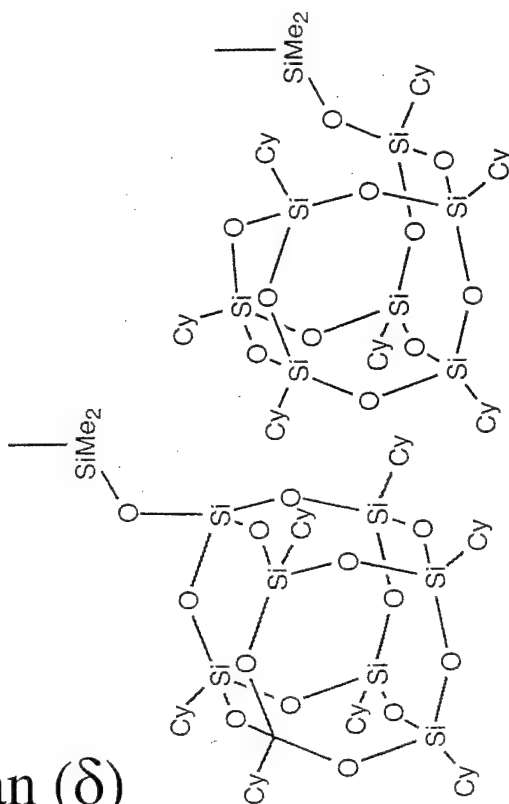


Comparison of Two POSS Polyhedra

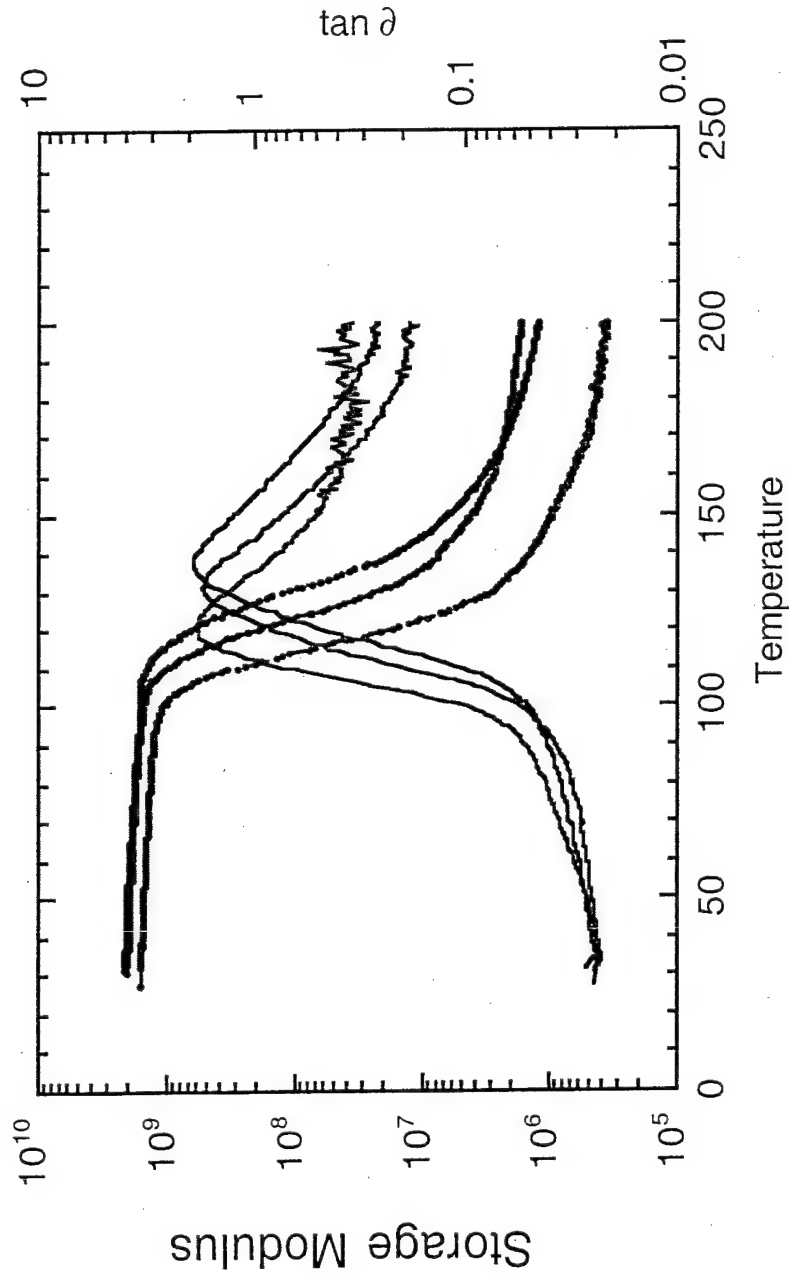


PDMS + 5 wt %
CyclohexylPOSS
Red = T8-POSS
Blue = T7-POSS

$\tan(\delta)$

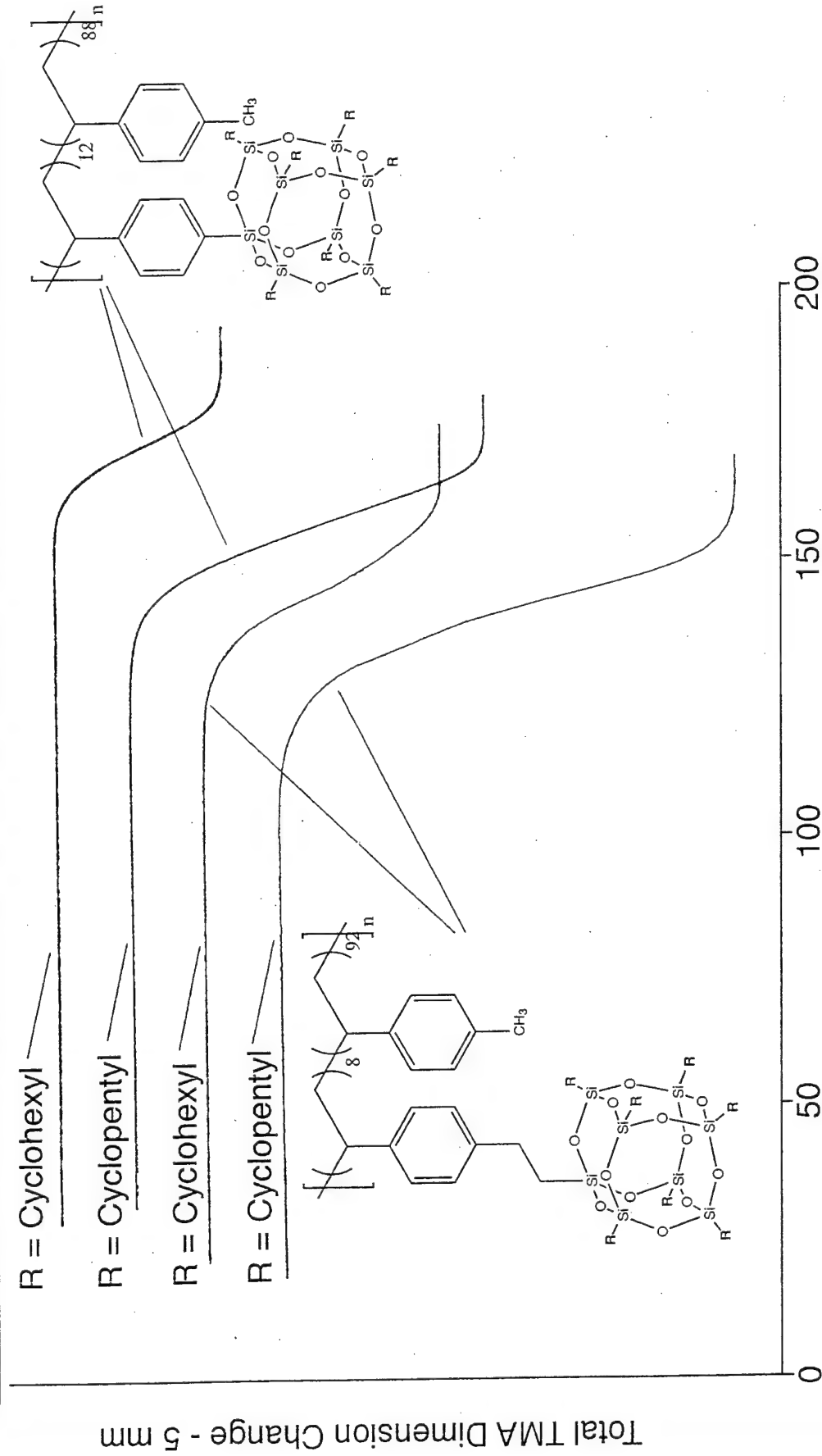


DMA of 30 wt % POSS Polystyrenes

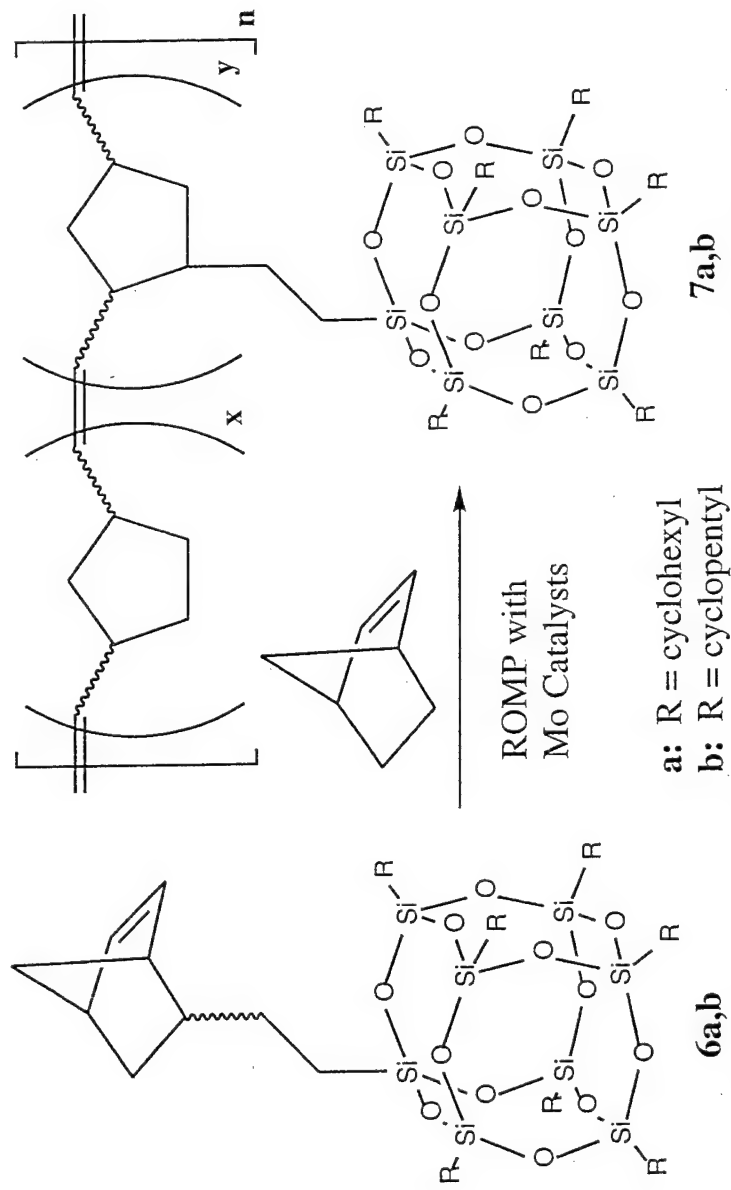


- Comparison of isobutyl, cyclopentyl & cyclohexyl
- Bulk polymerized samples

TMA Plot Comparison For POSS-Styryl and POSS-EthylStyryl Polymers (R = Cyclohexyl and Cyclopentyl)



Polymerization of POSS Norbornenes



Both block and random copolymers were synthesized.

The wt. % POSS was varied from 0 to 50 wt. % POSS.

An ideal polymerization would yield polymers with 500 monomer units.

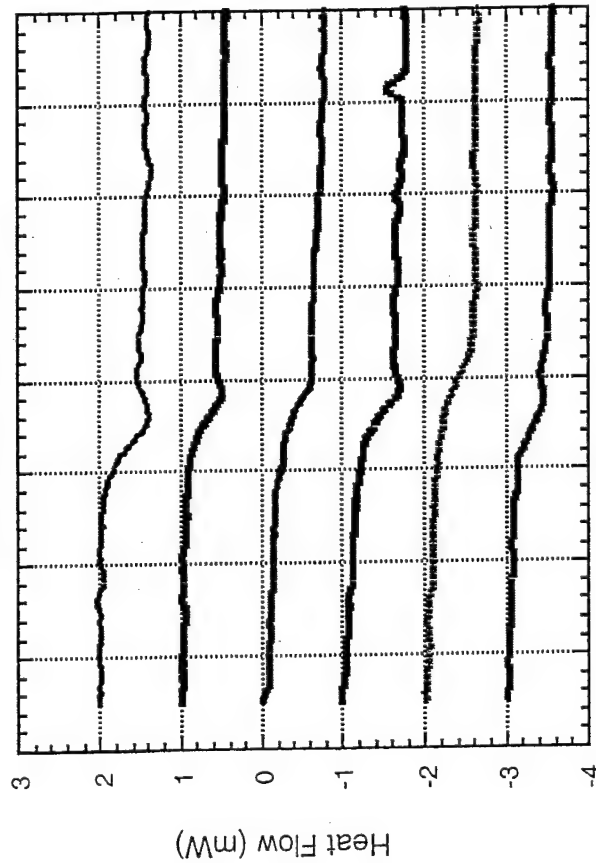
0 wt % POSS, 0 mole % POSS: $x = 500$, $y = 0$

10 wt % POSS, 1 mole % POSS: $x = 495$, $y = 5$

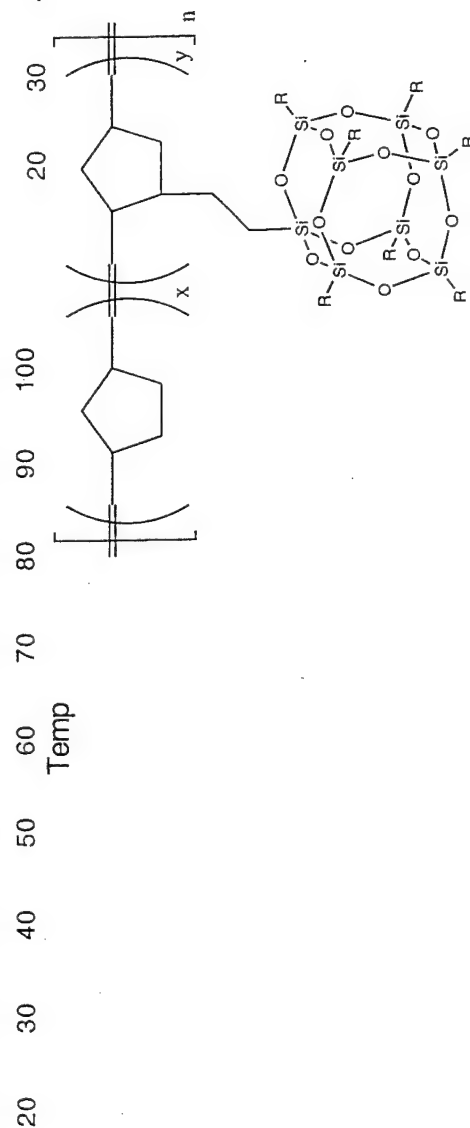
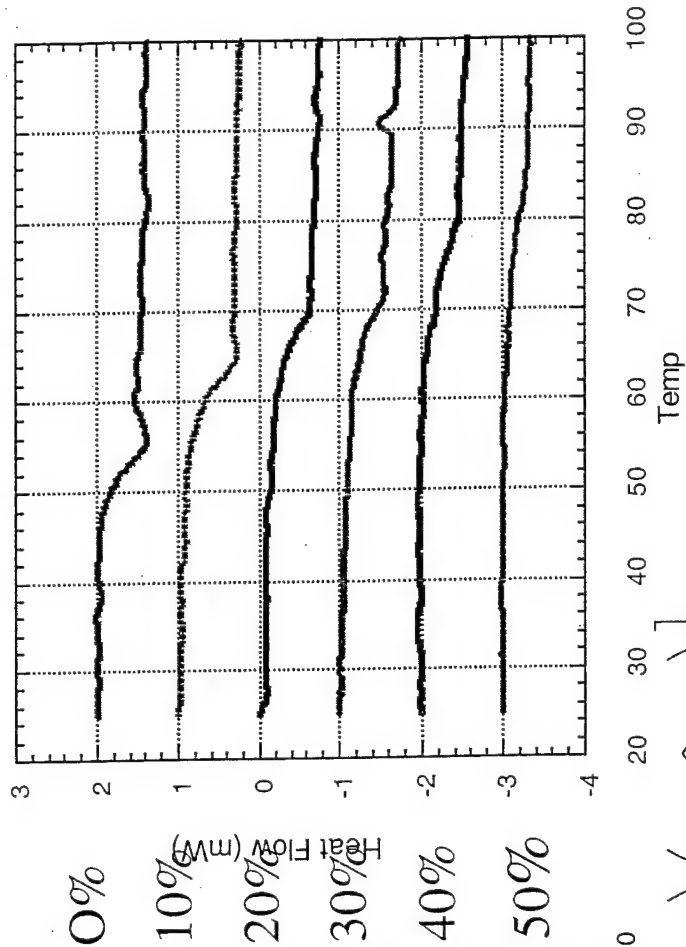
50 wt % POSS, 8 mole % POSS: $x = 460$, $y = 40$

DSC Data for POSS-Norbornenes

CyNorb(0-50)-block

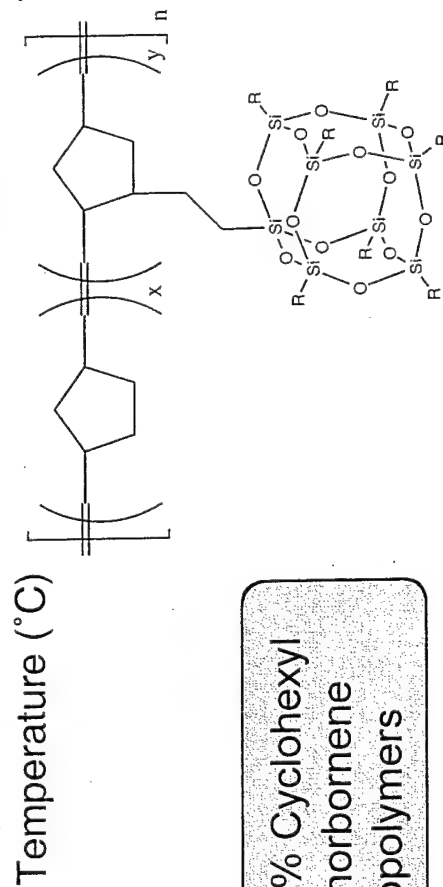
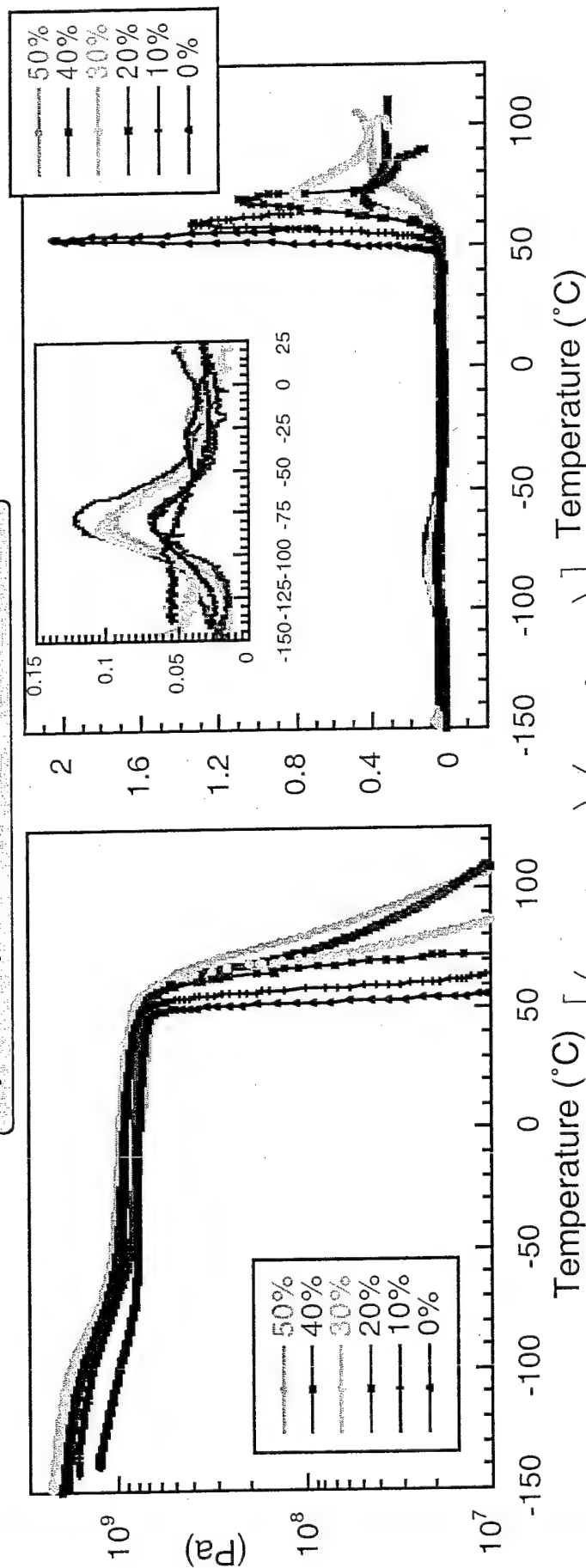


CyNorb(0-50)-random



Storage Modulus and Loss Tangent

Cyclohexyl Relaxation: 14.7 kcal/mol

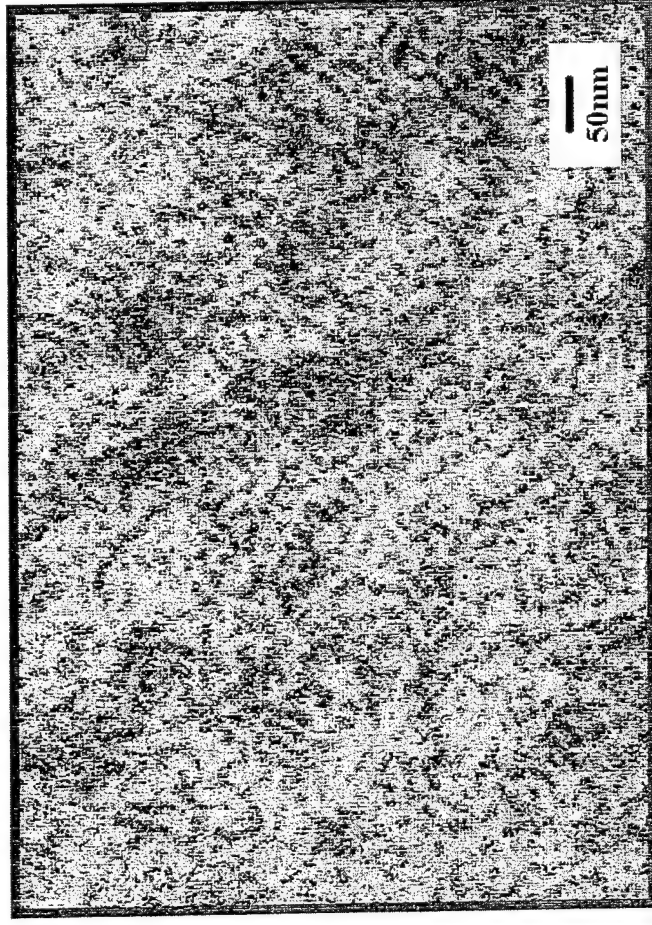


No Maximum for
50% CyPOSS

Various Wt % Cyclohexyl
POSS Polynorbornene
Random Copolymers

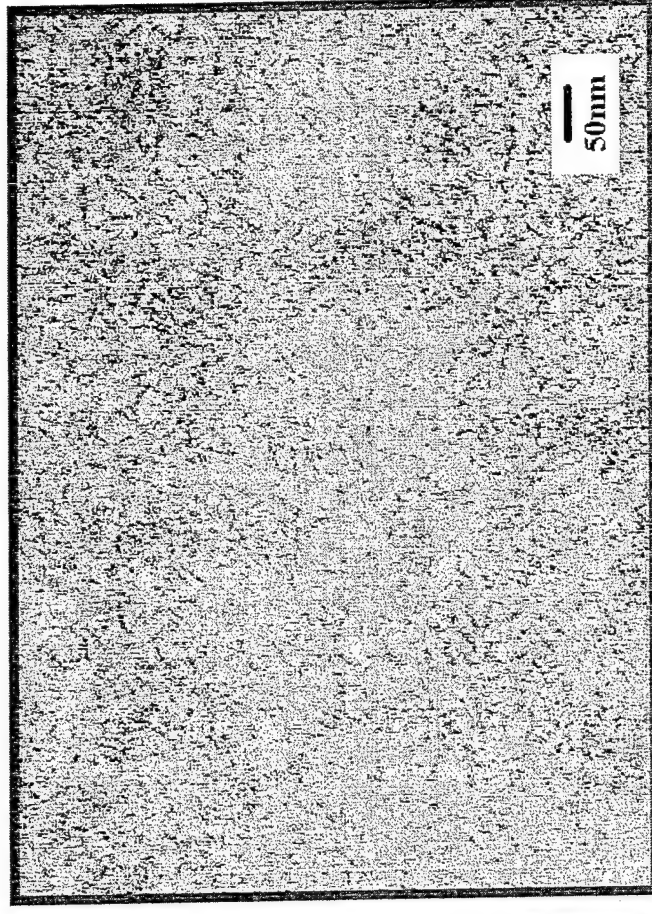
TEM of Random POSS Norbornenes

50CyPOSS/PN



“Coarse” Cylinder Nanostructure
(Diameter ~ 12nm)

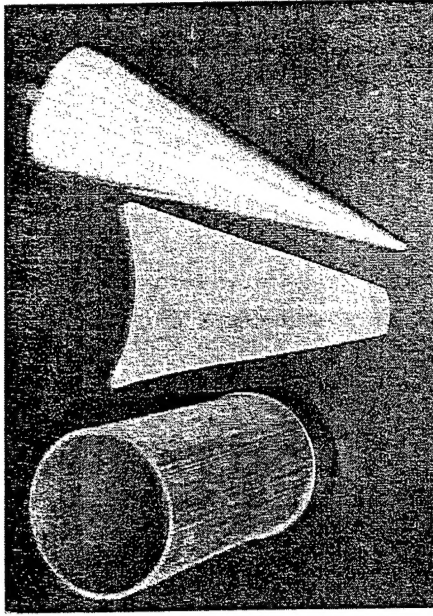
50CpPOSS/PN



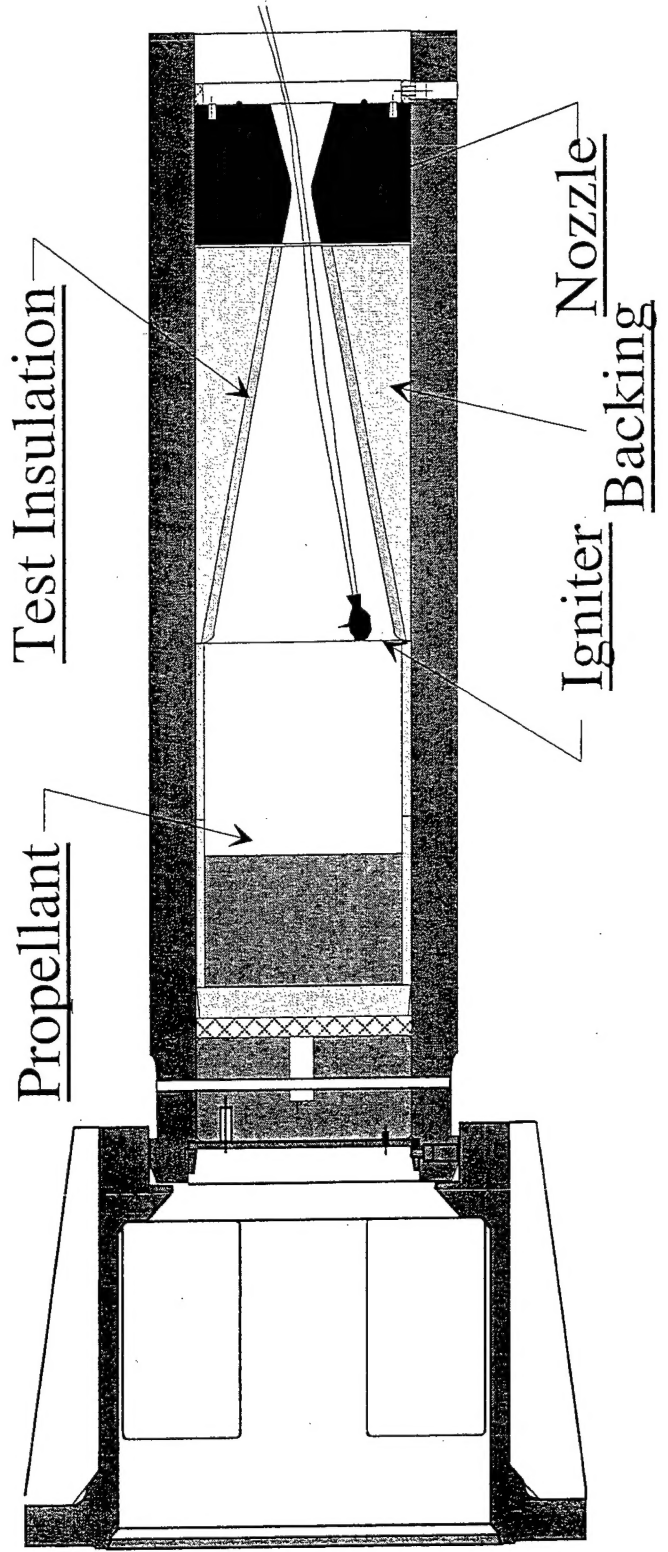
“Fine” Cylinder Nanostructure
(Diameter ~ 6nm)

CyclohexylPOSS-rich domains may entrain more unoriented polynorbornene chains than CyclopentylPOSS-rich domains.

Solid Rocket Motor Insulation

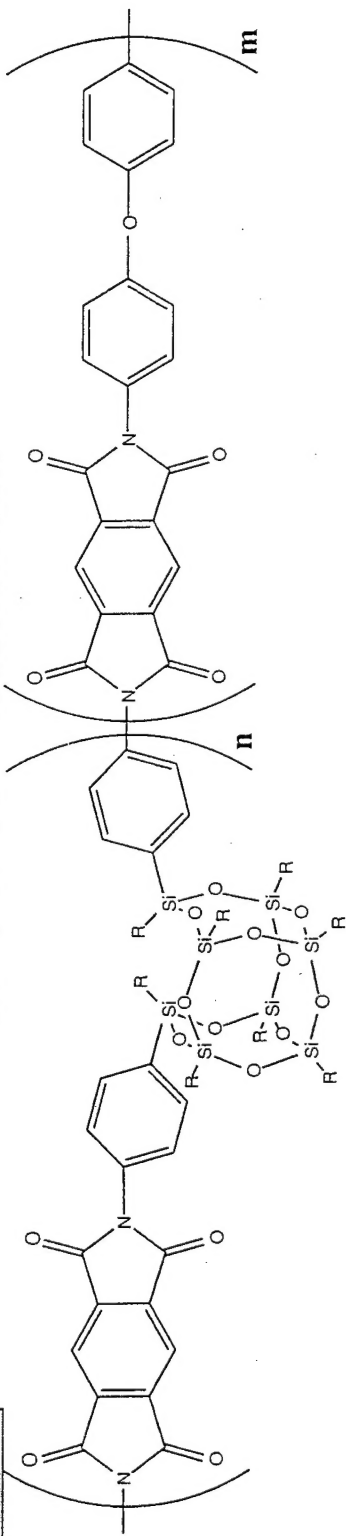


POSS-Insulation Sample



O-Atom Etching Experiment

8.47×10^{20} atoms cm^{-2}



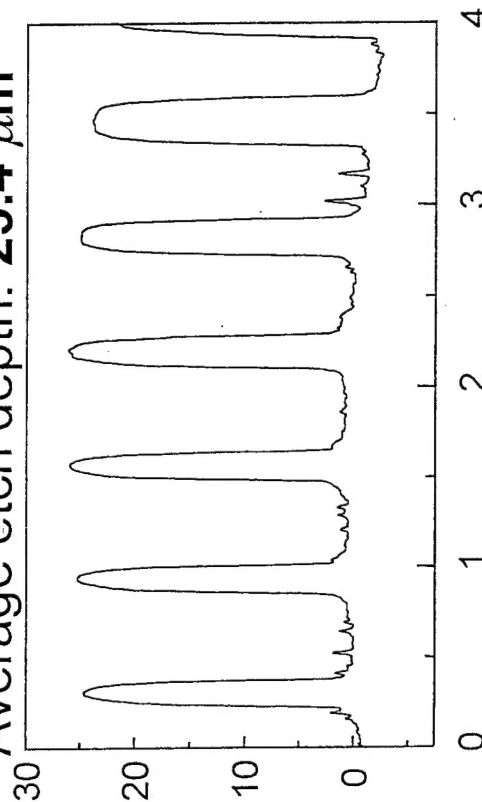
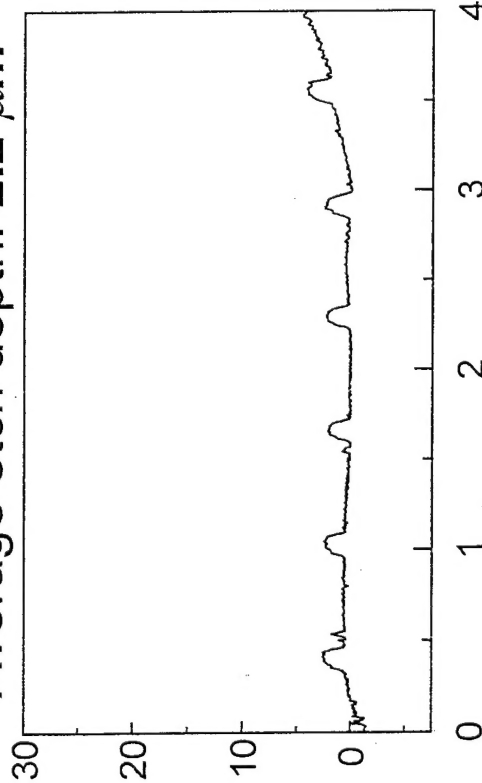
Kapton 10 wt% POSS

Average etch depth: $2.2 \mu\text{m}$

Kapton H Standard

Average etch depth: $25.4 \mu\text{m}$

Etch Depth (microns)



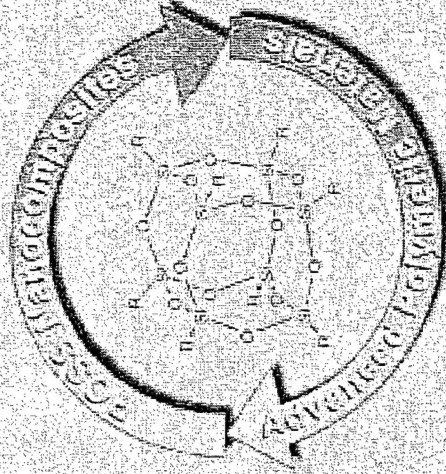
Scanning Length (mm)

Summary

- The successful incorporation of nano-sized inorganic clusters (POSS) into a wide variety of polymers has been demonstrated.
- These POSS clusters have a remarkable effect on the thermal transitions and mechanical properties of the polymers they are copolymerized into.
- The POSS effect on the properties of analogous polymers shows a dependency on the type of alkyl group on the POSS cluster.
- TEM images of randomly copolymerized polymers illustrate this dependency, as the size of the POSS domains are alkyl-group dependent.
- Rheology of high molecular weight PDMS grafted with small amounts of POSS illustrates a dependence on both the POSS-alkyl-group and POSS shape.

Acknowledgement\$

Dr. Brent Viers
Mr. Brian Moore
Mr. Justin Leland
Mr. Pat Ruth
Capt. Rene Gonzalez
Dr. Rusty Blanski
Dr. Shawn Phillips
Dr. Sandra Tomczak



Prof. Pat Mather UCONN
Prof. Andre Lee MSU
Prof. Ben Hsiao SUNY
Prof. Frank Feher UCI
Prof. Gar Hoflund UF
Prof. Tim Mitten MSU

Hybrid Plastics Inc.

Acknowledgement\$: We gratefully acknowledge the Air Force Office of Scientific Research, Directorate of Chemistry and Life Sciences, and the Air Force Research Laboratory, Propulsion Directorate for their financial support.